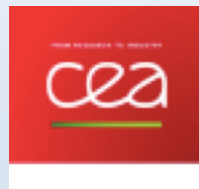


Ultrafast dynamics of hot carriers in bulk semiconductors and in accumulation layer: energy loss rate and screening effects.

Jelena Sjakste

*Laboratoire des Solides Irradiés, CNRS, Ecole Polytechnique, CEA/DRF/IRAMIS
Institut Polytechnique de Paris, France*



Collaborations

Ecole Polytechnique, LSI:

N. Vast,

R. Sen (post-doc)

L. Perfetti (ARPES, 2PPE)



Osaka, Japan:

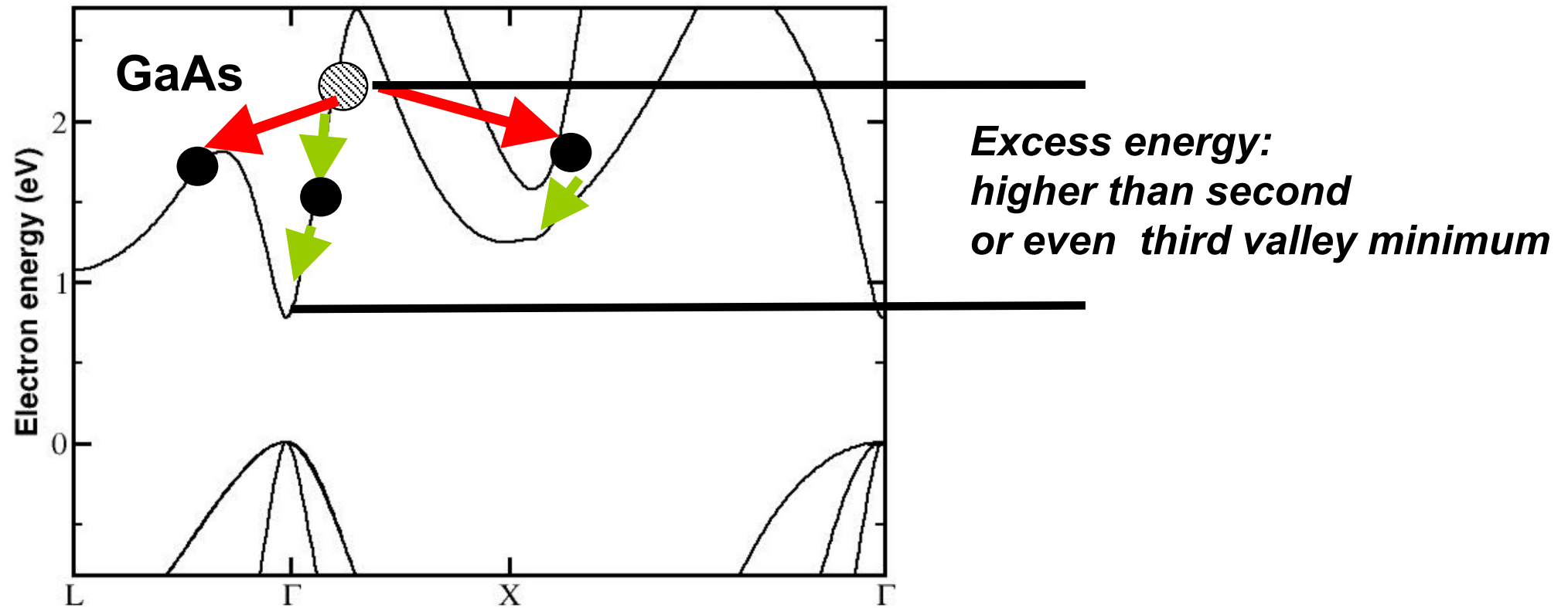
K. Tanimura (ARPES, 2PPE)



Outline

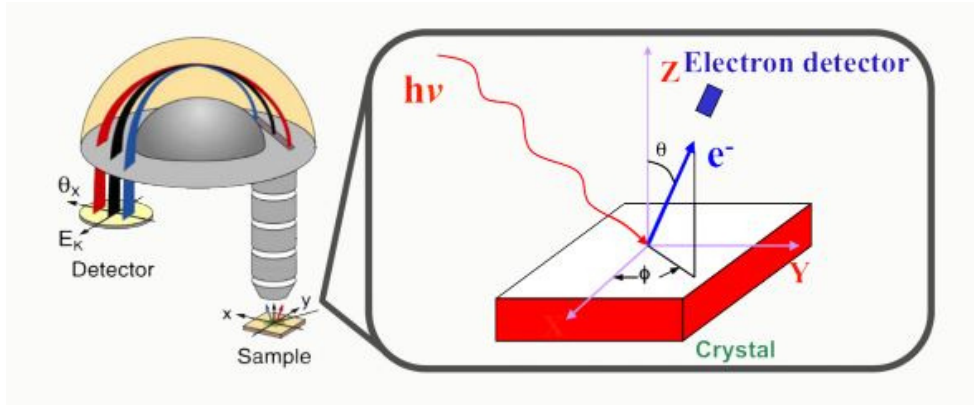
- ***Electron-phonon scattering for highly excited electrons***
- ***Highly excited electron relaxation in Si***
- ***Photoexcited electron relaxation in InSe***

RELAXATION DYNAMICS OF HIGHLY EXCITED ELECTRONS



Main scattering mechanism: intervalley electron-phonon scattering

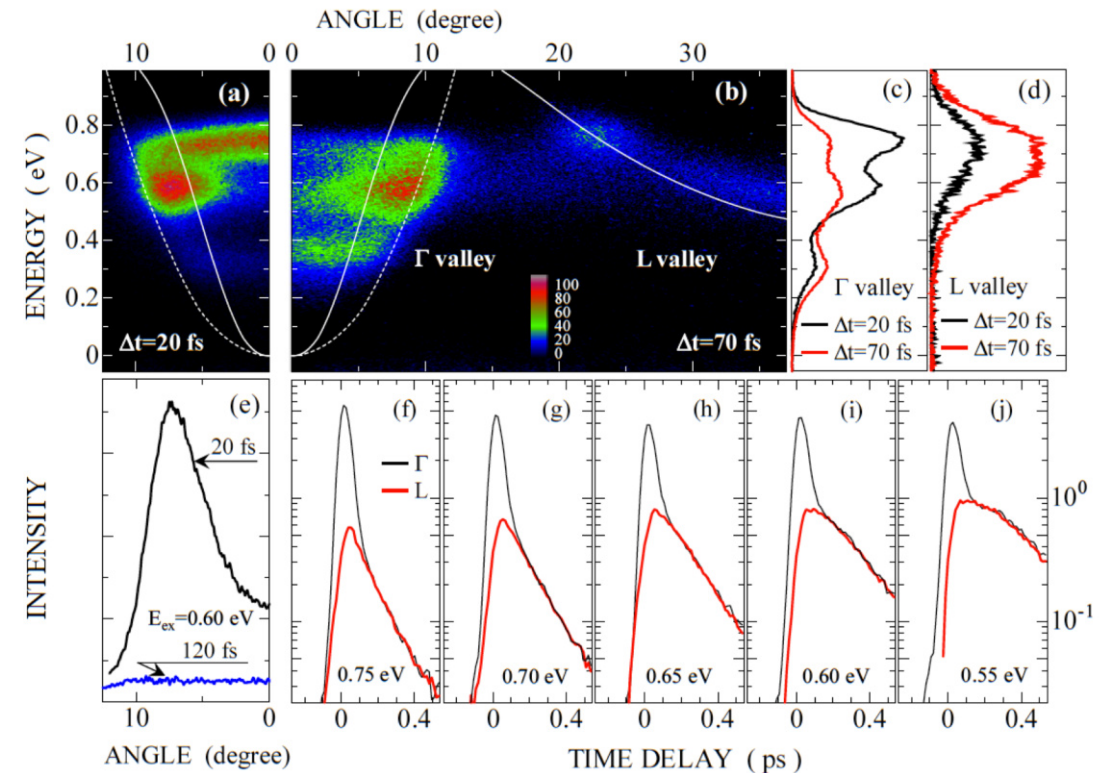
EXPERIMENTS: ARPES



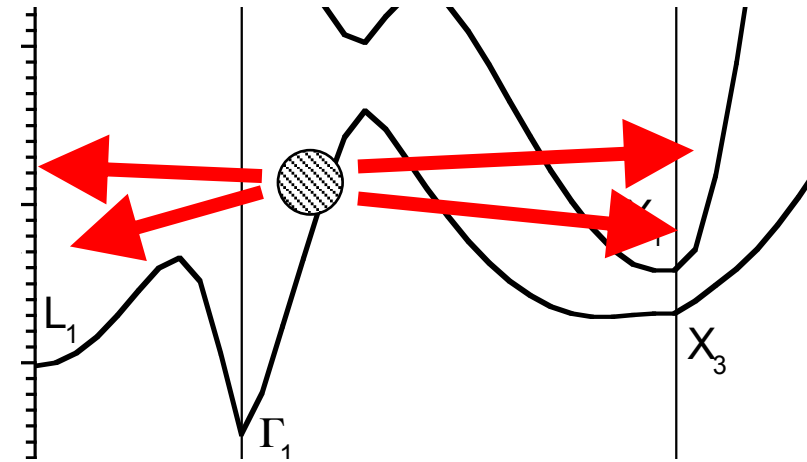
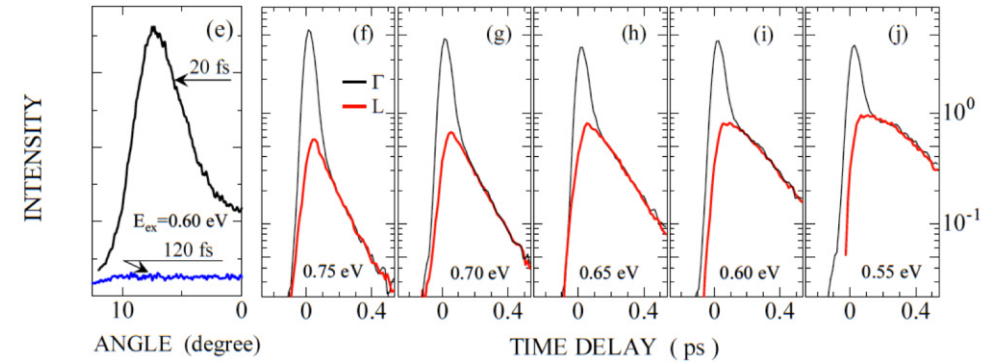
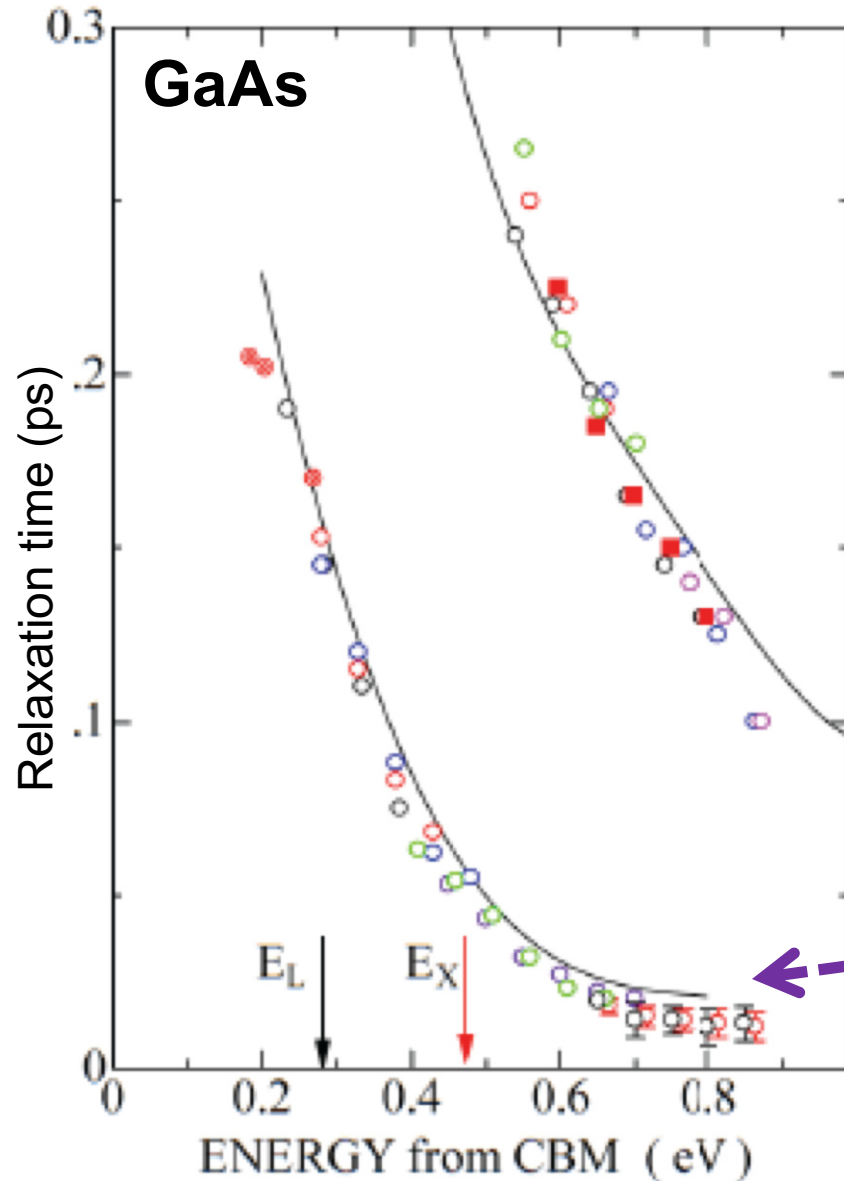
Pump and probe: 2 laser pulses at different time

GaAs
300K

Two distinct relaxation regimes



HOT ELECTRON ENSEMBLE (HEE)

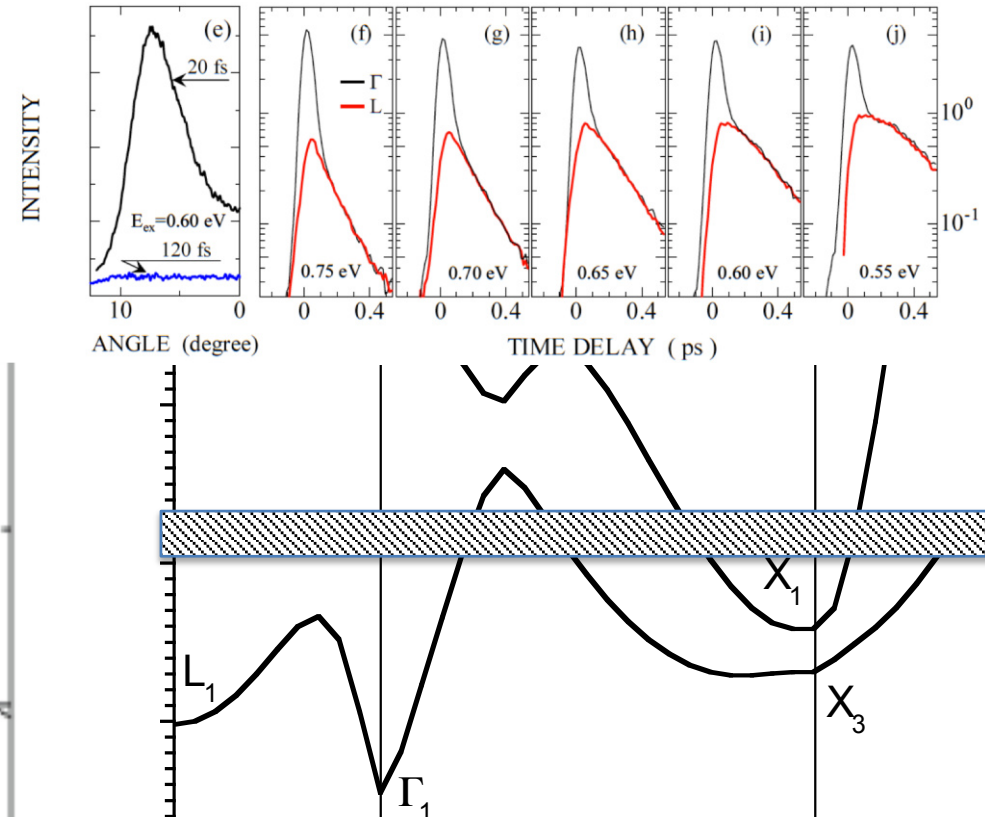
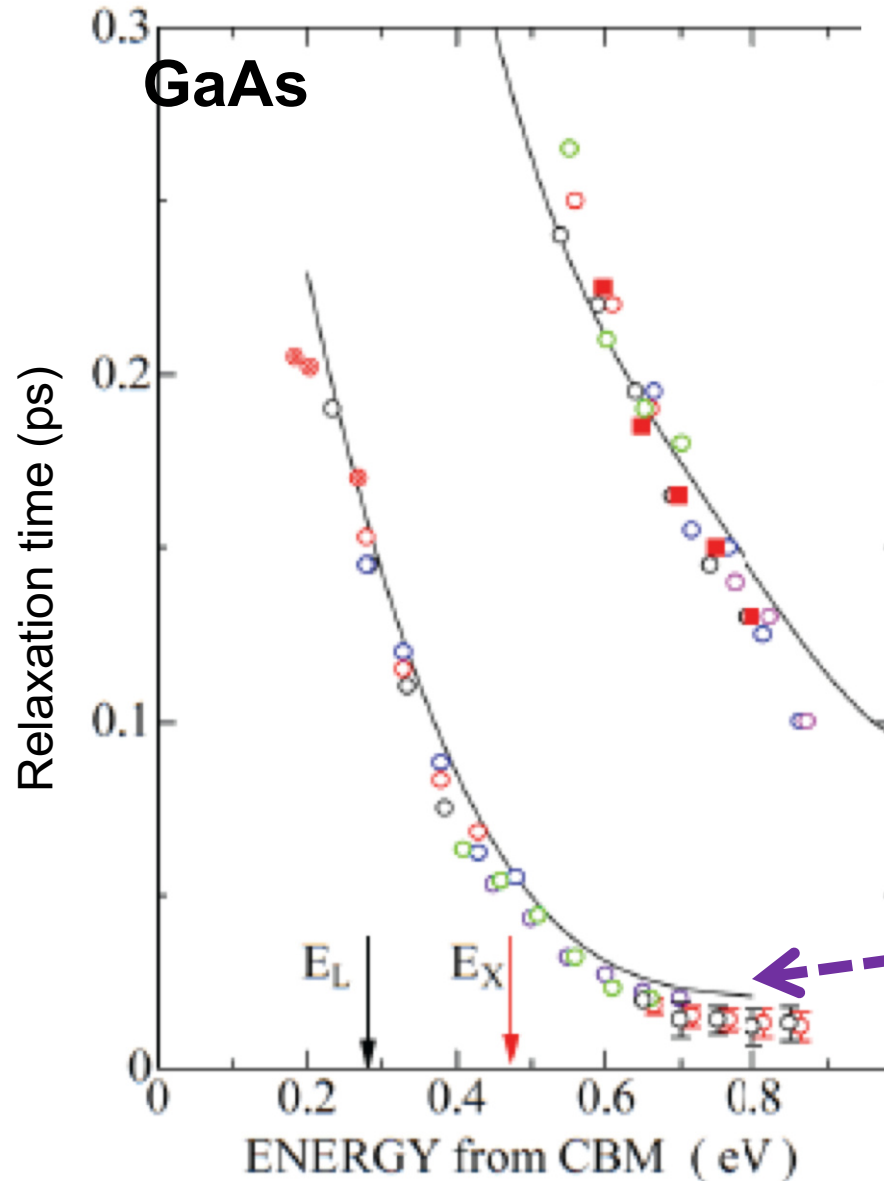


« Short » time: wavepacket spreads over BZ;
 « isomerization »: total scattering rate,
 mostly intervalley transitions

Tanimura et al, *PRB* 93 (2016) 161203 (R).

Sjakste et al, *J. Phys: Cond. Mat.* **30**, 353001 (2018).

HOT ELECTRON ENSEMBLE (HEE)

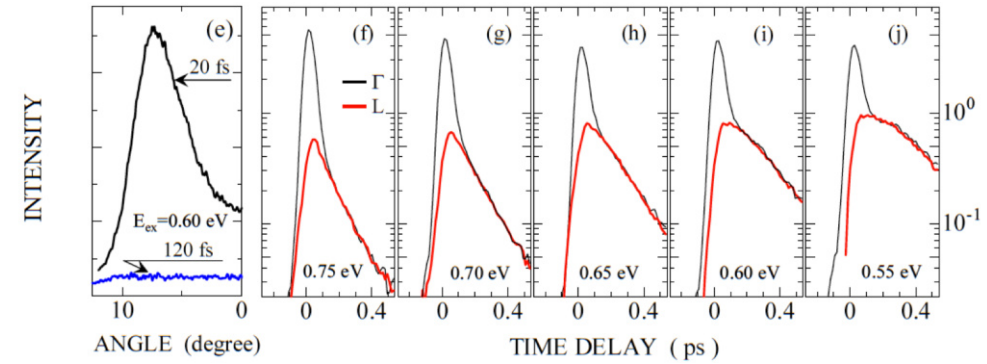
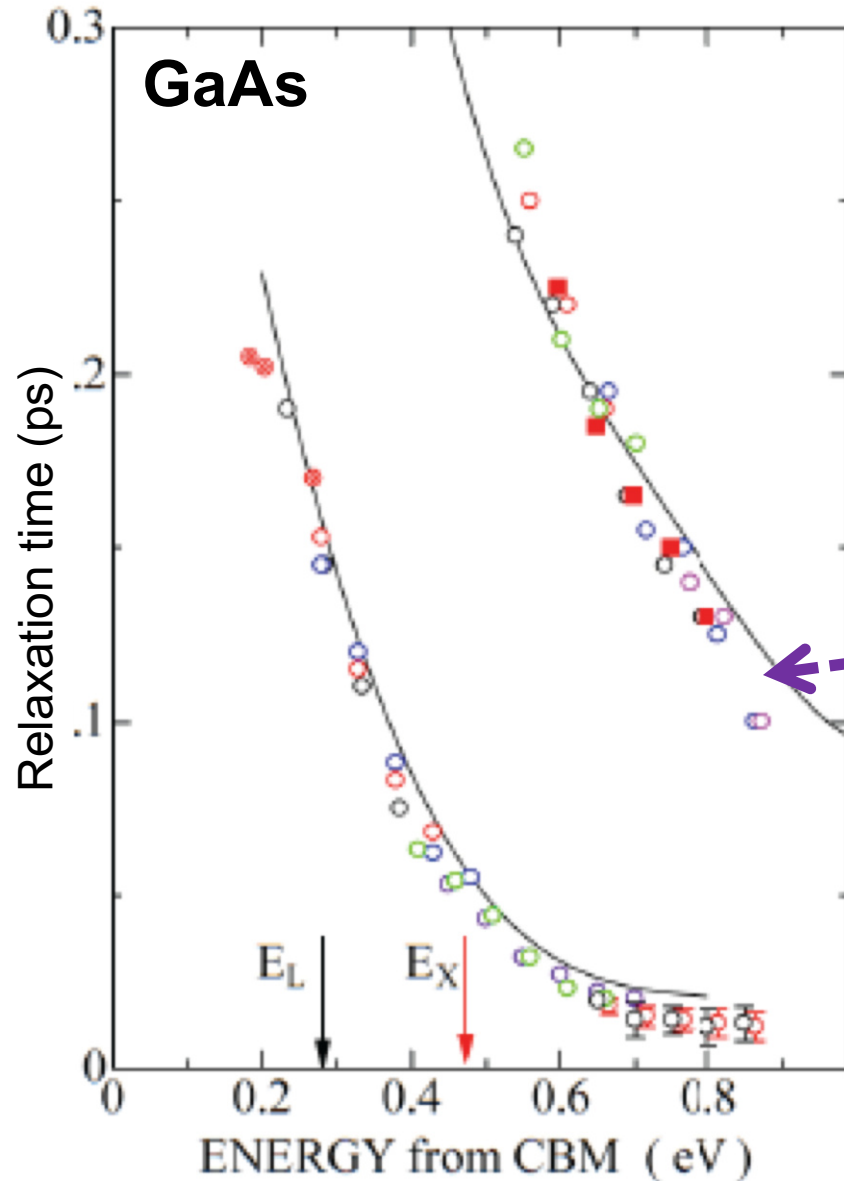


« Short » time: wavepacket spreads over BZ;
 « isomerization »: total scattering rate
 mostly intervalley transitions

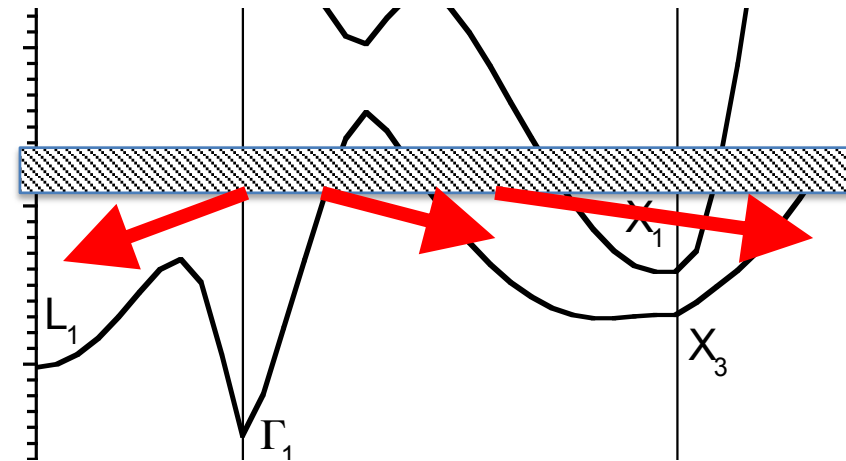
Tanimura et al, PRB 93 (2016) 161203 (R).

Sjakste et al, J. Phys: Cond. Mat. **30**, 353001 (2018).

HOT ELECTRON ENSEMBLE (HEE)



« long » time: energy transfer to phonons



mostly intervalley transitions

Tanimura, Kanasaki, Tanimura, Sjakste, Vast, Calandra, Mauri, PRB 93 (2016) 161203 (R).

CALCULATIONS: DFPT+Wannier

Reciprocal space
Bloch functions
Initial grid

$$\langle \Psi_{n,k} | \Delta W_q^\lambda | \Psi_{n',k+q} \rangle - \text{Non-local part (if polar)}$$



Real space
Maximally localized Wannier functions
Interpolation on dense grid



Reciprocal space
Bloch functions
Dense grid

$$\langle \Psi_{n,k} | \Delta W_q^\lambda | \Psi_{n',k+q} \rangle + \text{Non-local part (if polar)}$$

J. Sjakste, N. Vast, M. Calandra, F. Mauri, PRB 92 (2015) 054307

C. Verdi, F. Giustino, PRL 115 (2015) 176401



Outline

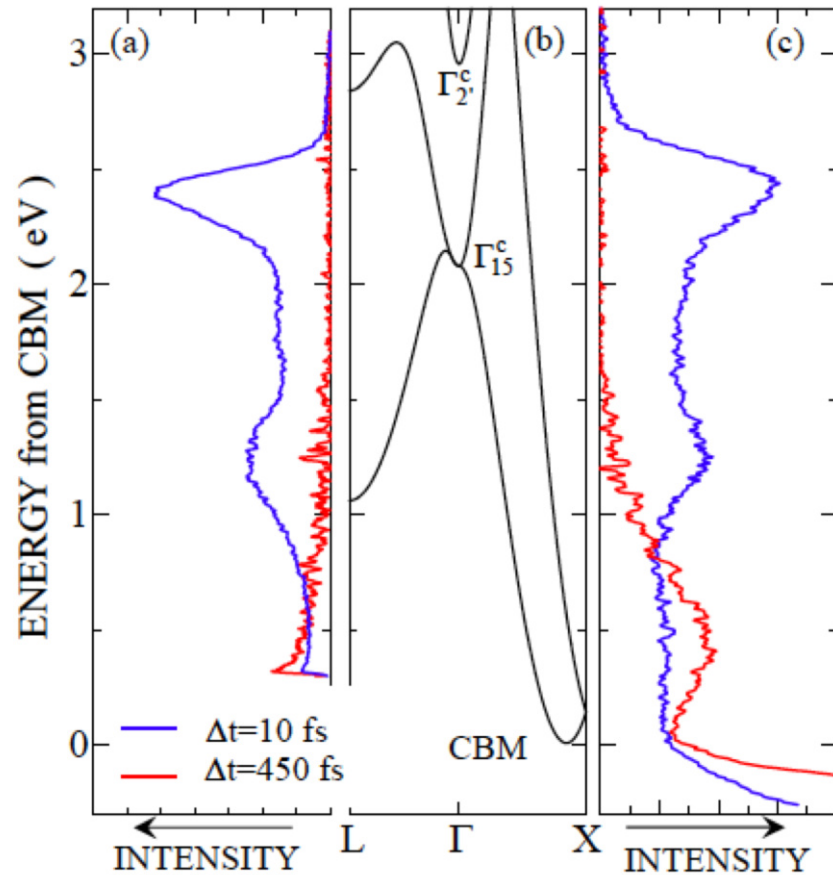
- ***Electron-phonon scattering for highly excited electrons***



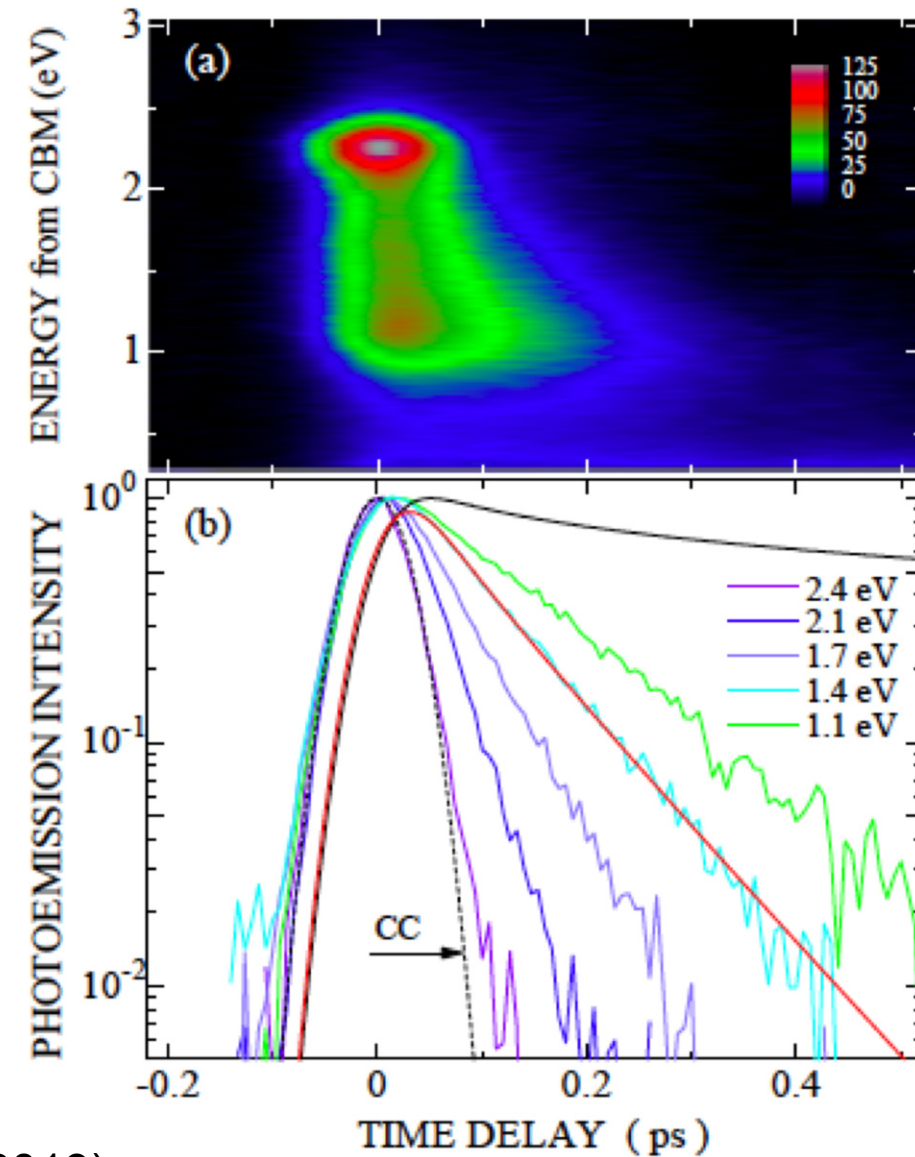
- ***Highly excited electron relaxation in Si***

- ***Photoexcited electron relaxation in InSe***

HIGHLY EXCITED ELECTRONS IN SILICON: 2PPE



Excess energies: 1-3 eV above CBM

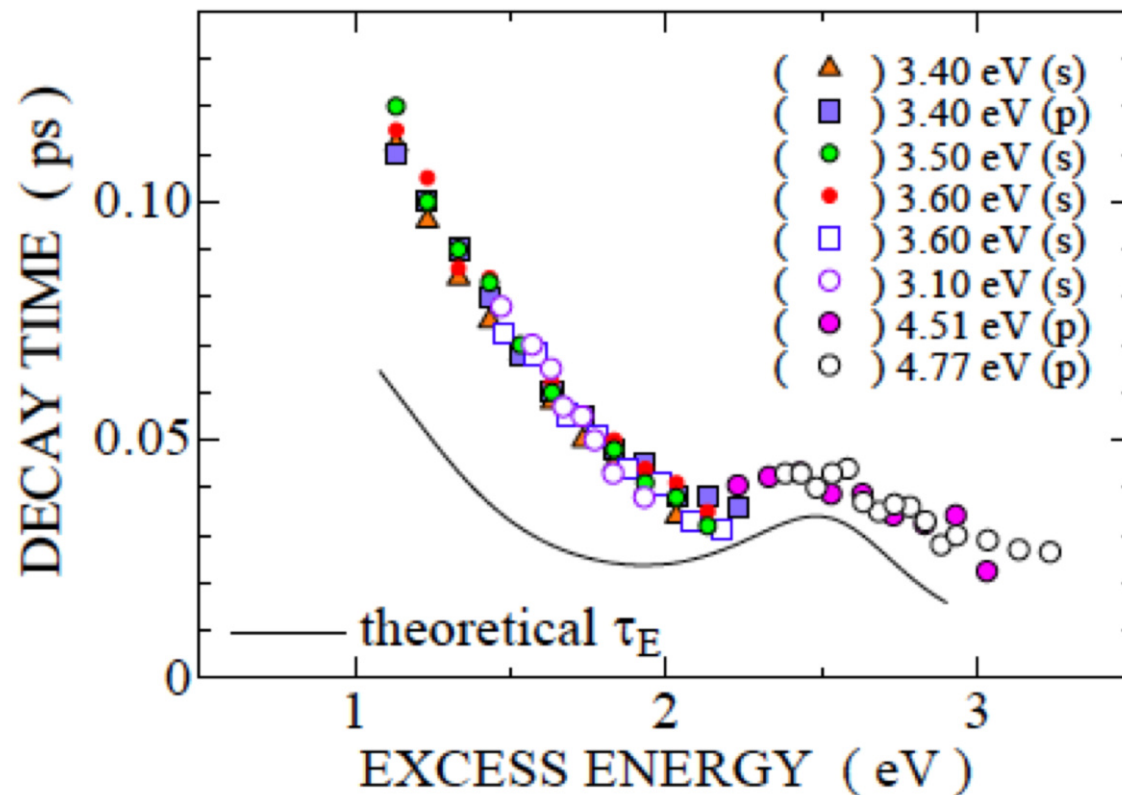


HIGHLY EXCITED ELECTRONS IN SILICON: INTERPRETATION PROBLEM

Previous work: conflict theory/experiment:

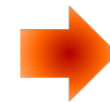
Measured relaxation times 10 times longer than calculated ones

Ichibayashi et al, Phys. Rev. B 84, 235210 (2011).



Tanimura, Kanasaki, Tanimura, Sjakste, Vast PRB **100**, 03520 (2019).

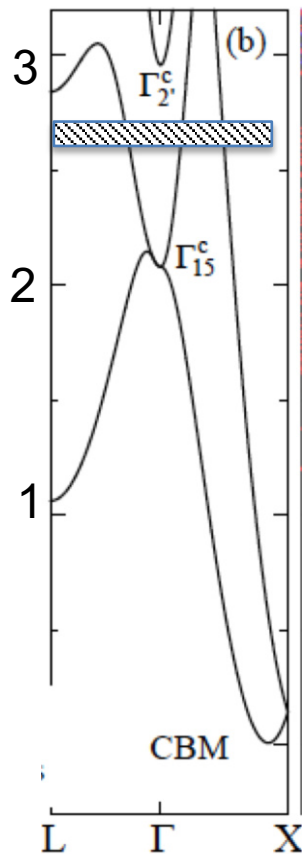
This work: HEE idea



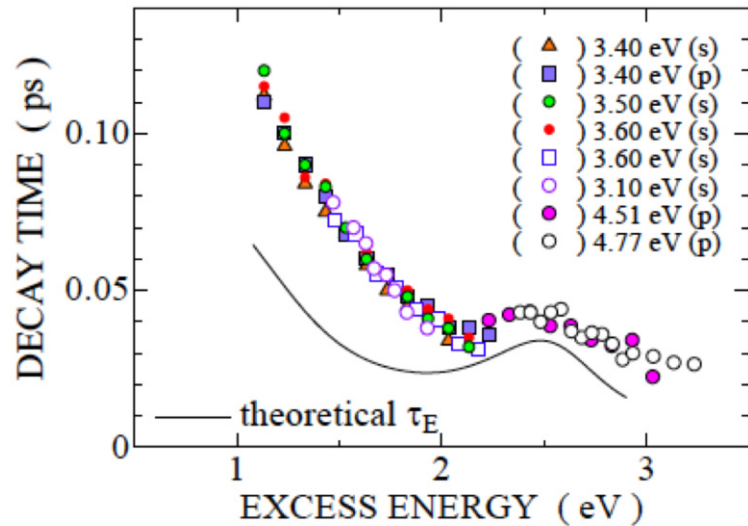
Initial relaxation:
too fast to be measured



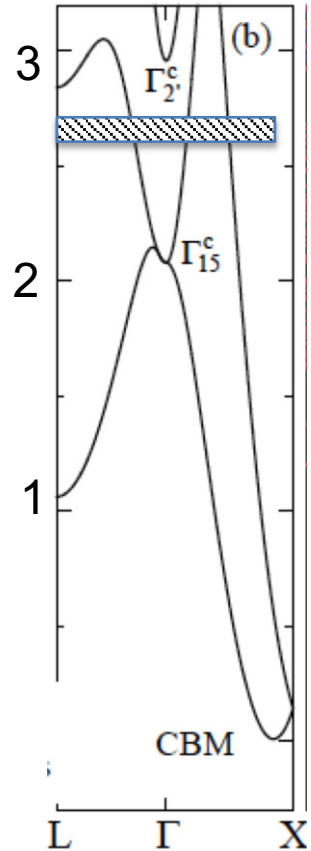
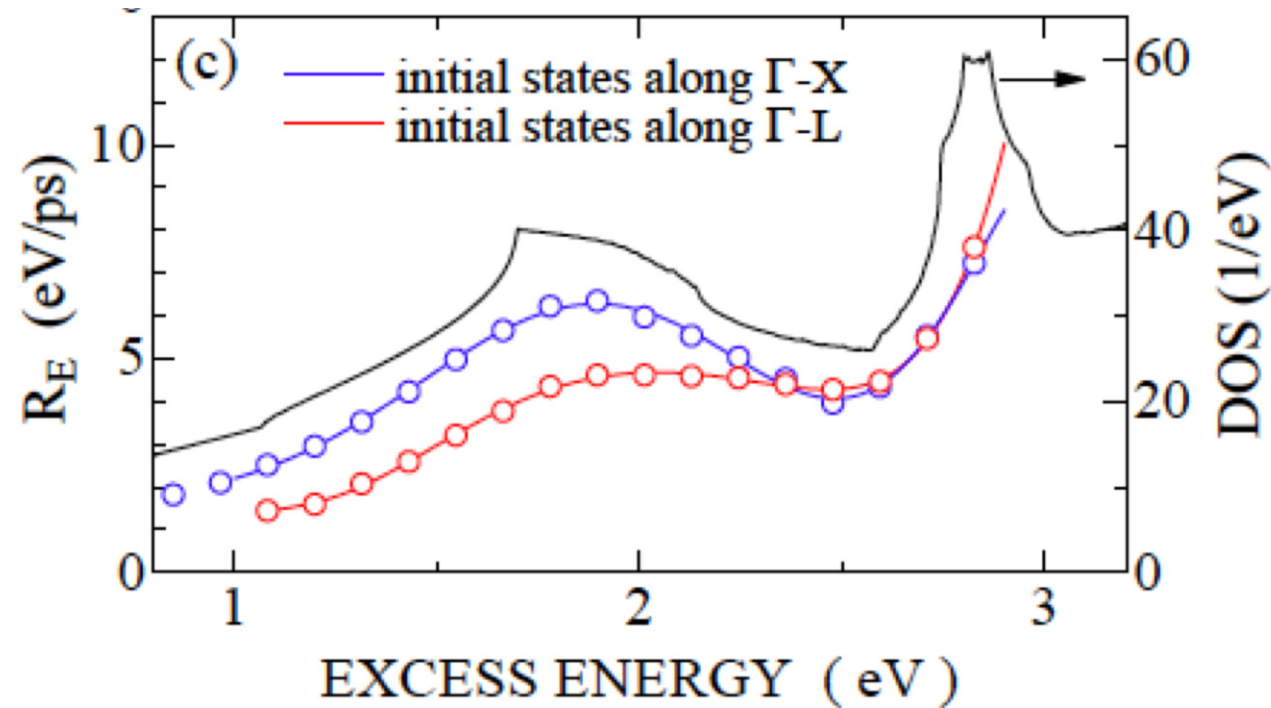
Measured relaxation times:
energy loss



HIGHLY EXCITED ELECTRONS IN SILICON: ENERGY LOSS RATE



$$dE / \tau_E = \Gamma_{em} \omega_{em} - \Gamma_{abs} \omega_{abs}$$



Energy loss rate:
Determined by DOS of final electronic states

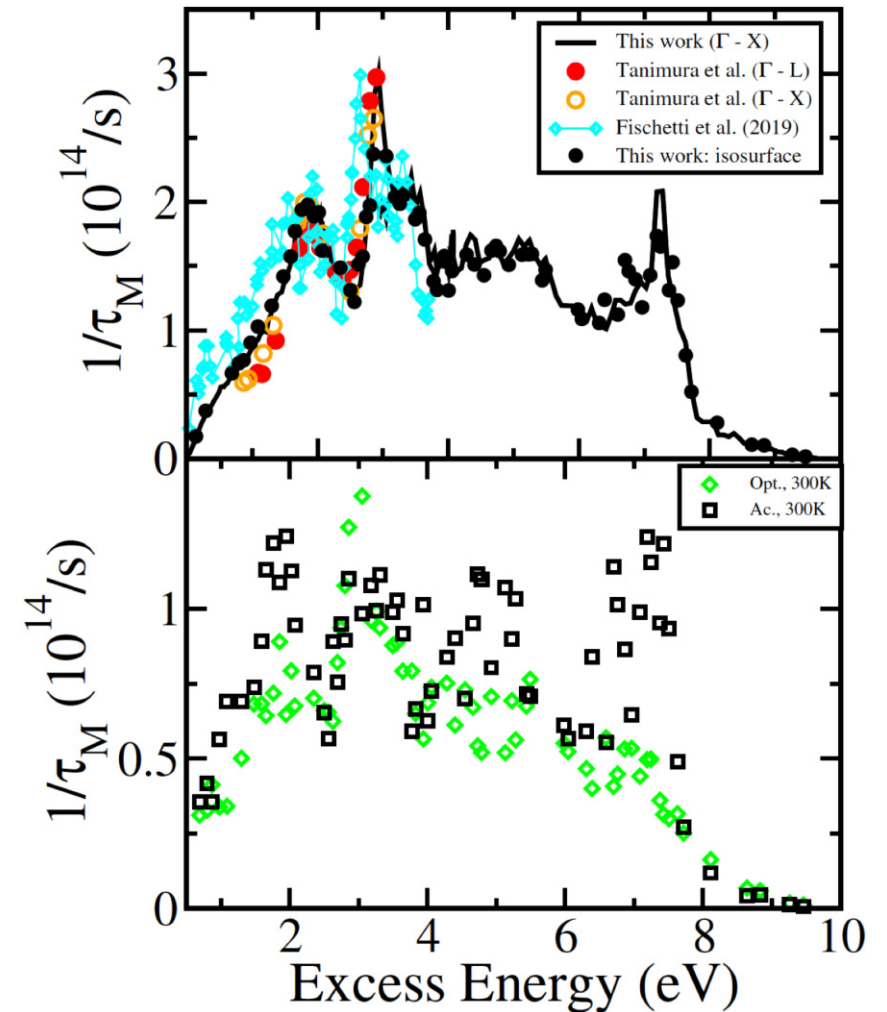
MAIN CHANNELS: IMPORTANT FOR MONTE CARLO



Raja Sen

**Total scattering rate:
acoustical phonons are dominant (at 300K)**

Si, 300 K



EPW code, EPIK code: identical results

Also: Bernardi et al, PRL (2014)

MAIN CHANNELS: IMPORTANT FOR MONTE CARLO



Raja Sen

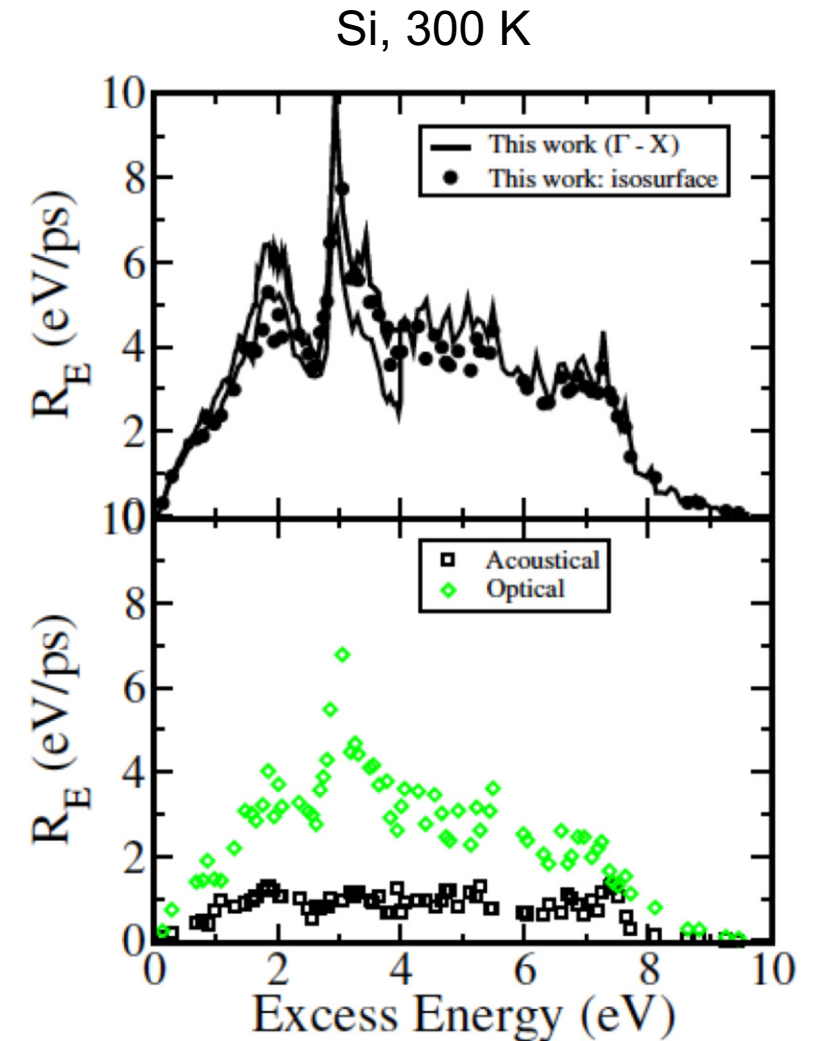
**Energy loss rate:
optical phonons are dominant**

Not unexpected:

Ahmad et al, Phys. Stat. Sol. 40:631 (1970)

**Temperature-dependent contribution of
acoustical phonons cancels out of energy loss**

EPW code, EPIK code: identical results

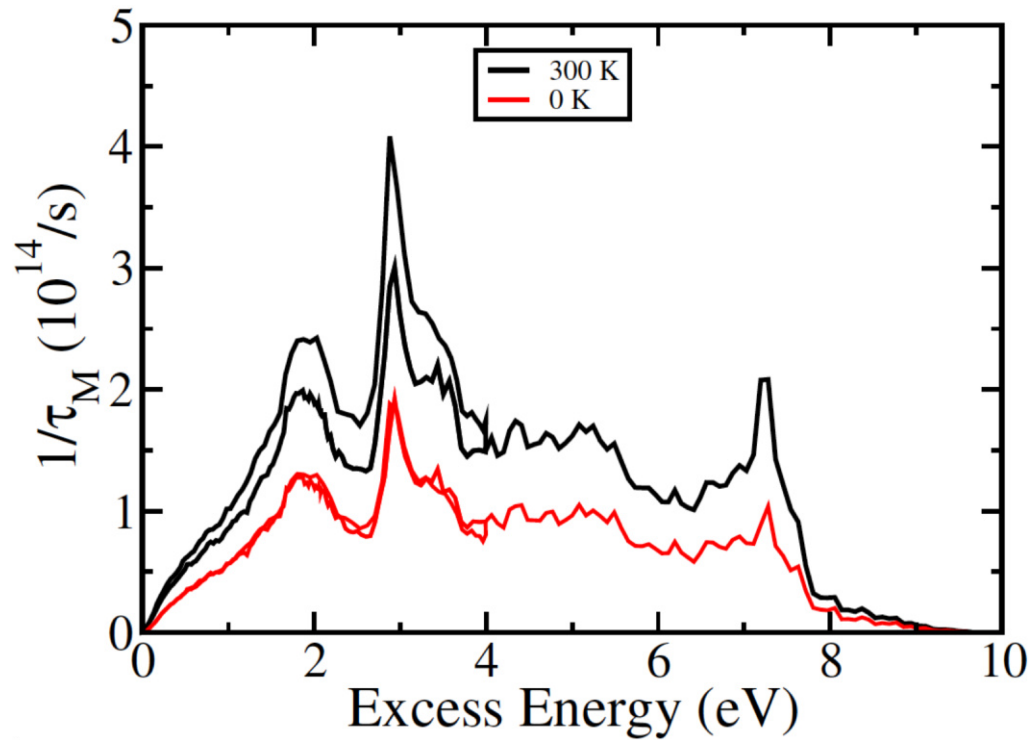


TEMPERATURE DEPENDENCE



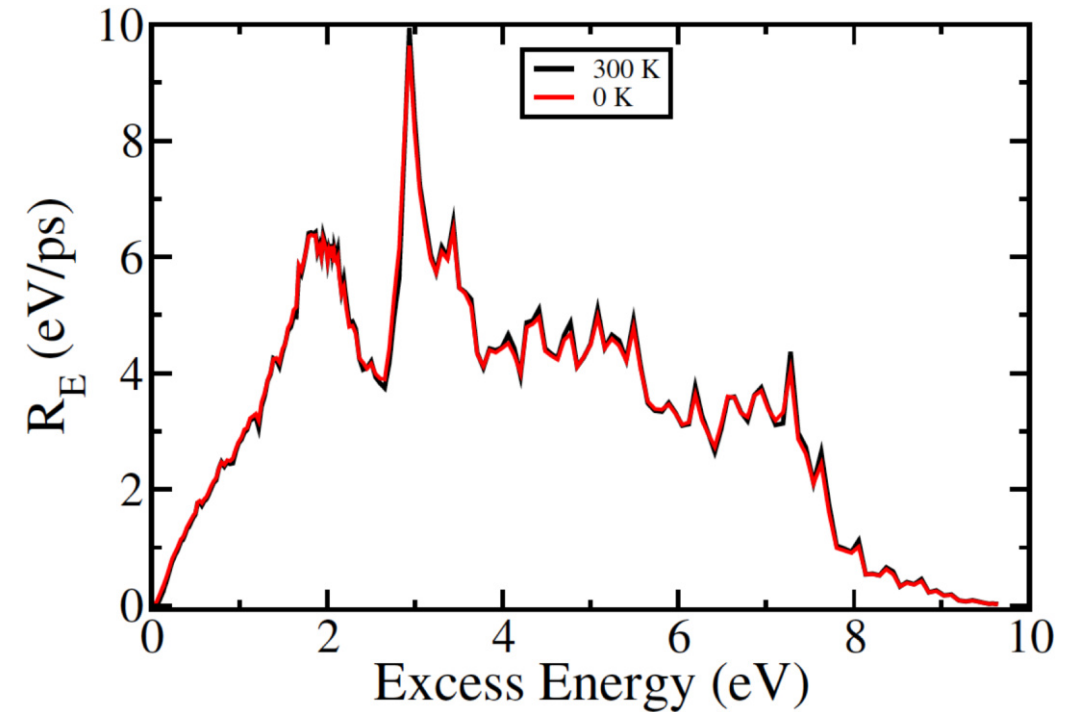
Raja Sen, post-doc

Total scattering rate, Si



Populations of acoustical phonons grow with temperature

Energy loss rate, Si.



Negligible temperature dependence for energy loss rate

Outline

- ***Electron-phonon scattering: general picture***
- ***Electron-phonon scattering for highly excited electrons***
- ***Highly excited electron relaxation in Si***
-  - ***Photoexcited electron relaxation in InSe***

Photoexcited electron relaxation in InSe

Luca PERFETTI
Zhesheng CHEN
Zailan ZHANG
Raphael CABOUAT
Jelena SJAKSTE
Cristine GIORGETTI
Valerie VENIARD
Abdelkarim Ouerghi
Hugo Henck

Evangelos PAPALAZAROU
Marino MARSI



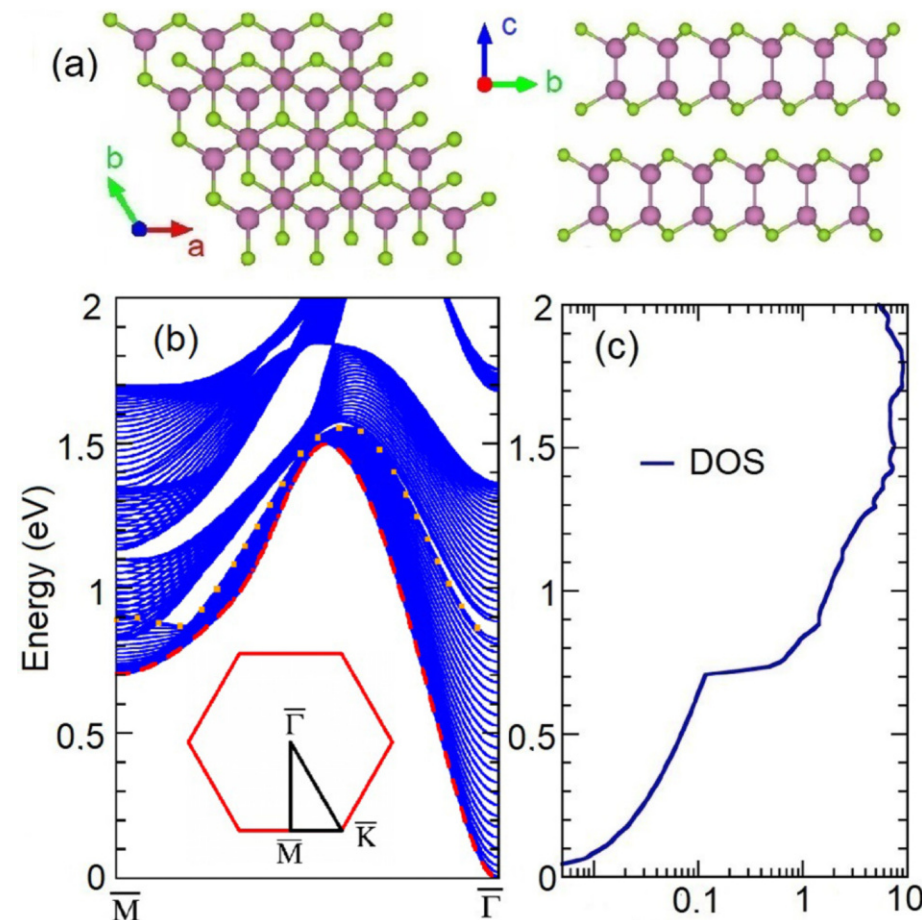
Layered material



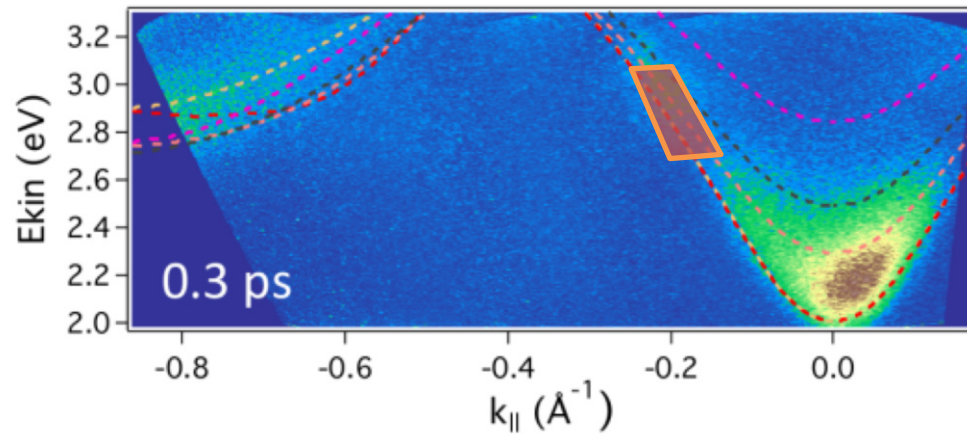
Very narrow Γ valley



Large M valley

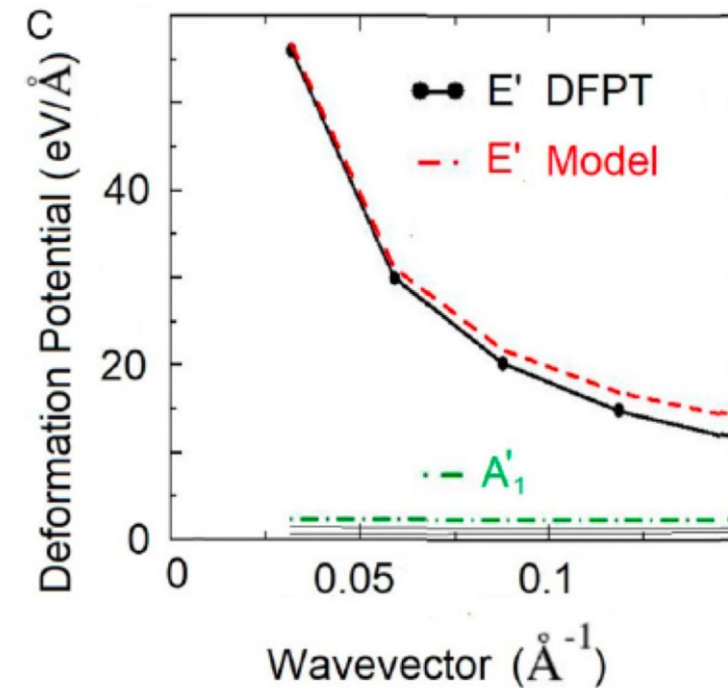


InSe: energy relaxation in Γ valley

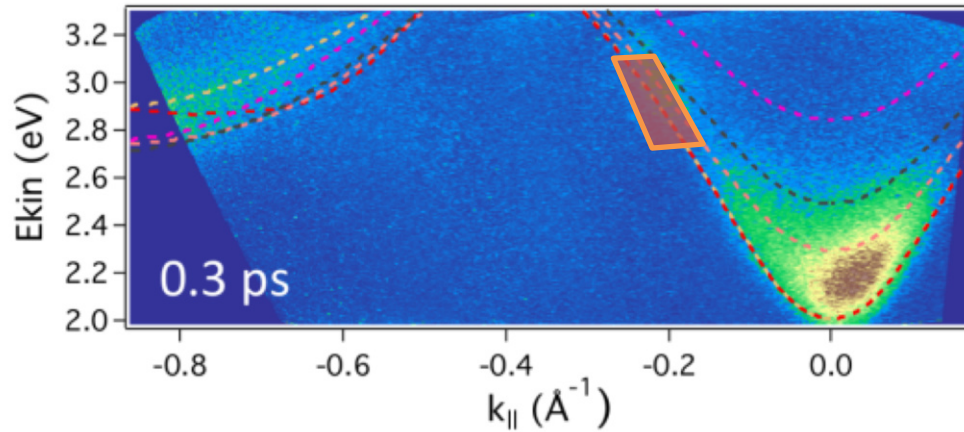


Excess energy below 0.7eV

- ➔ no intervalley scattering
- ➔ very narrow Γ valley ($q < 0.2$ ang.)
- ➔ **Fröhlich scattering**
(scattering by polar phonons)

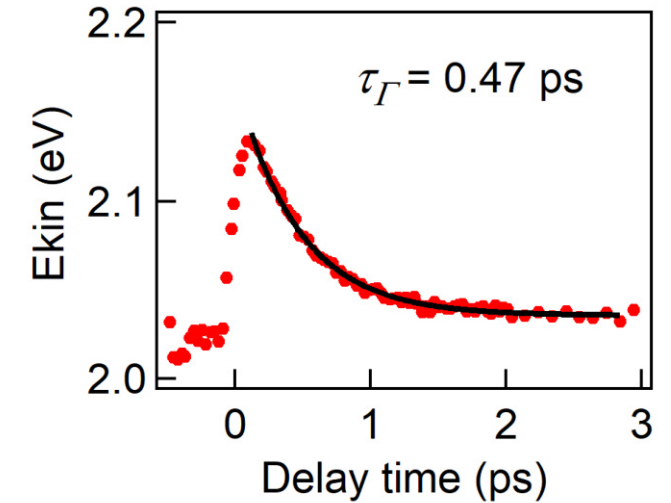


InSe: energy relaxation in Γ valley

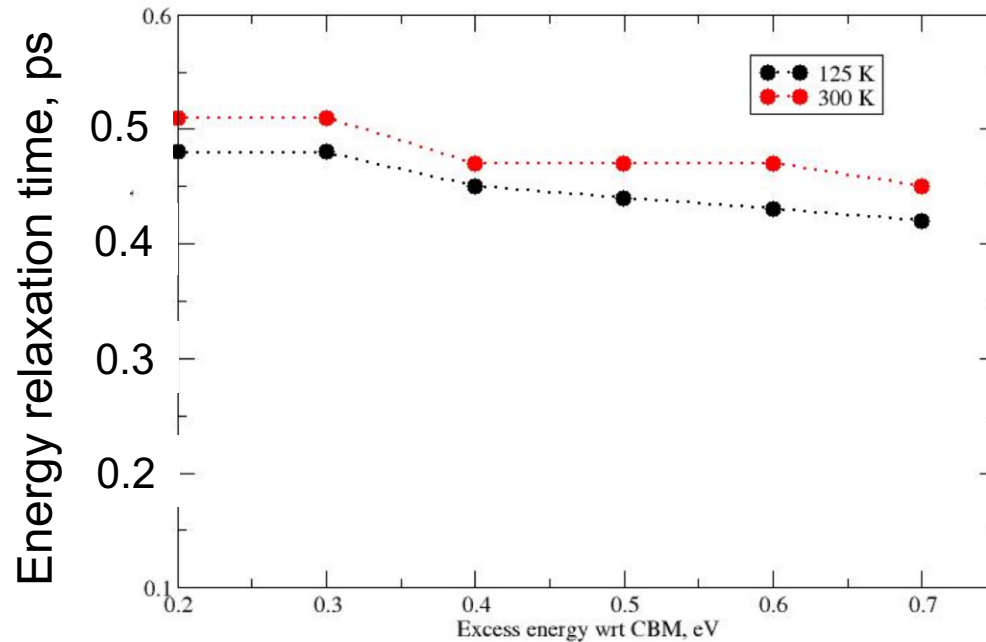


below 0.7 eV

Experiment



Theory: energy transfer due to coupling with polar phonons



scattering by polar phonons

$$\frac{4\pi e}{\epsilon_{\infty} q^2} q_{\mu} \sum_{\alpha} Z_{\mu\lambda}(\alpha) e_{\lambda}(\alpha \hat{q})$$

➡ Good agreement between theory and experiment.

Quasi-two-dimensional gas on InSe

Experiment:

Zhesheng CHEN
Luca PERFETTI

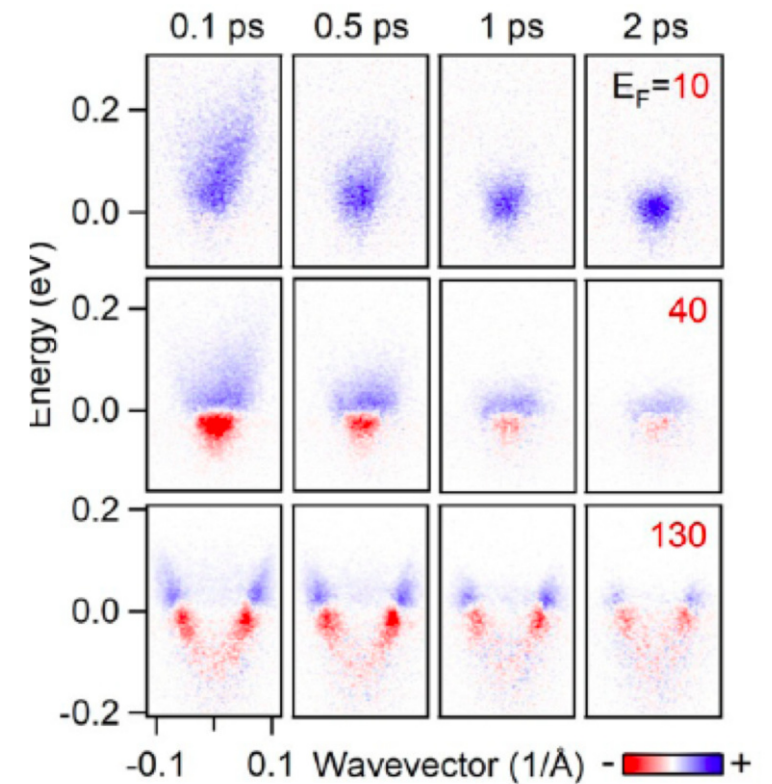
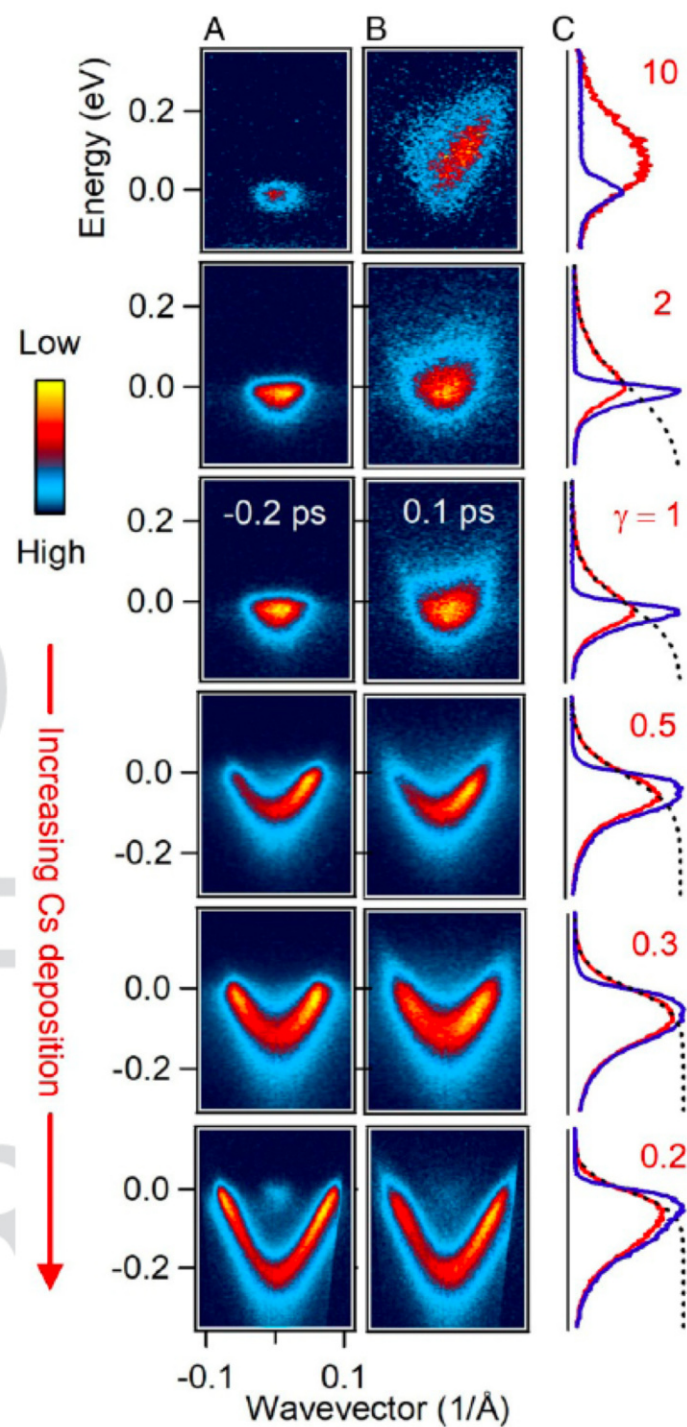


★ Increasing Cs deposition on
InSe surface



electron gas created on the
surface

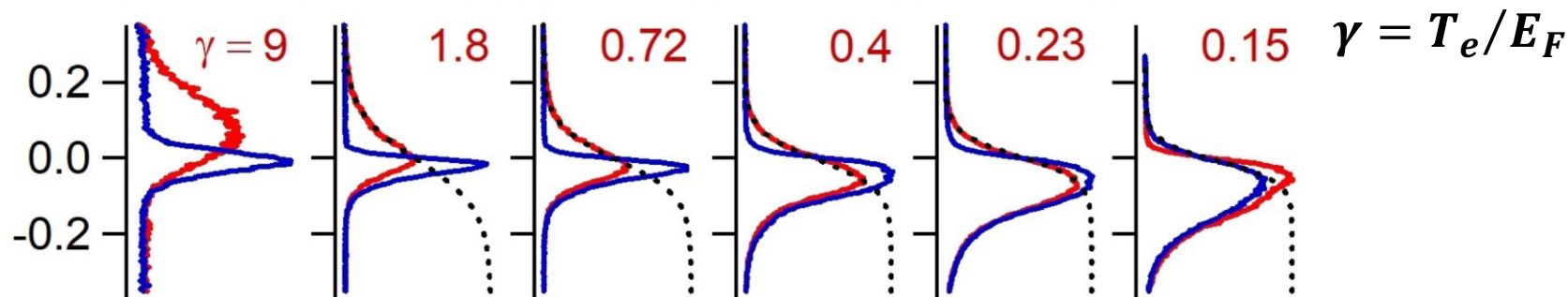
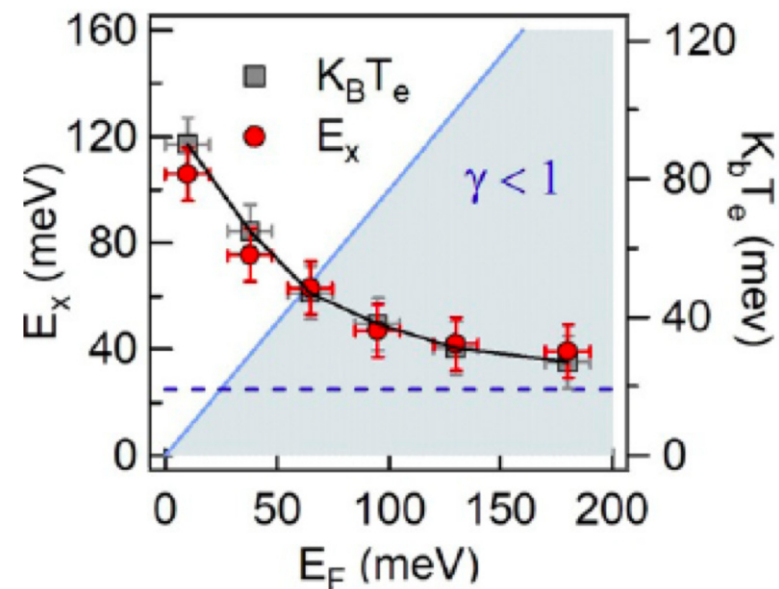
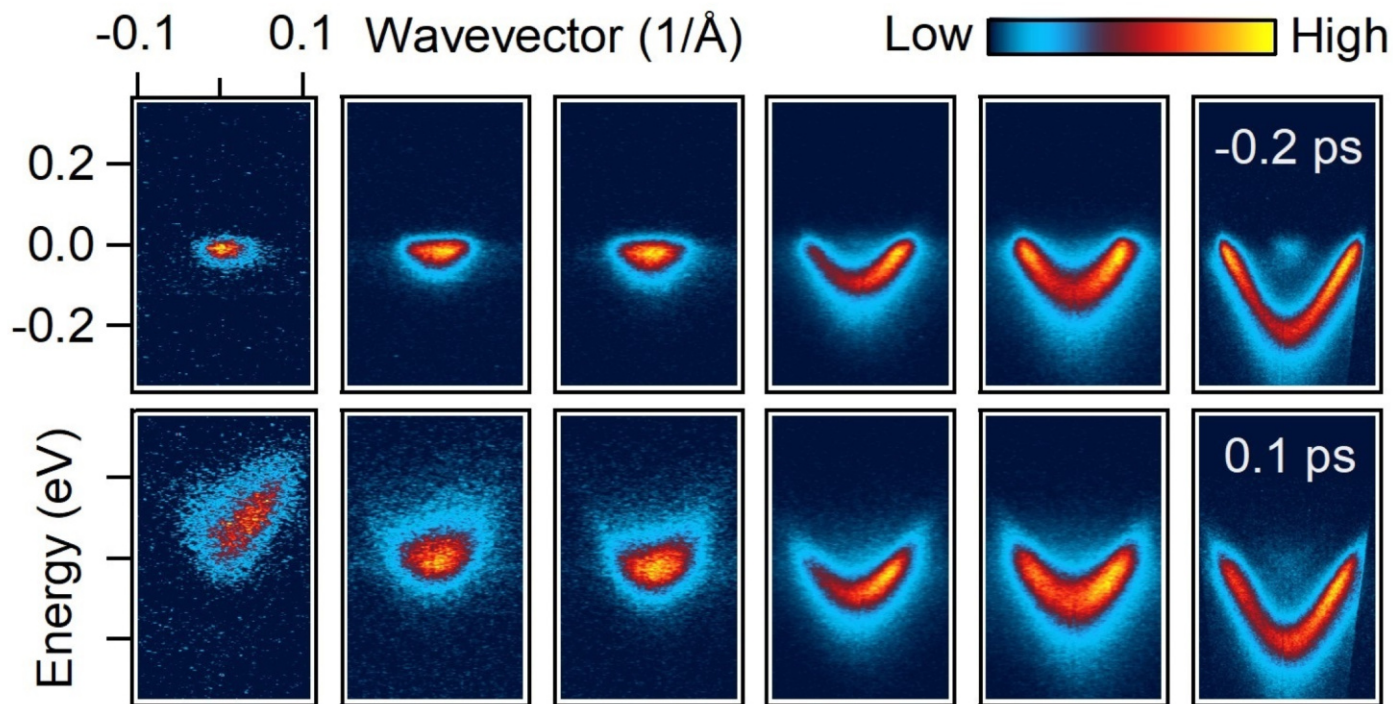
★ Dynamics of excited electrons
studied by tr-ARPES



C

Chen, Sjakste et al, PNAS 117, 21962-21967 (2020)

Photoexcited electrons and 2D gas

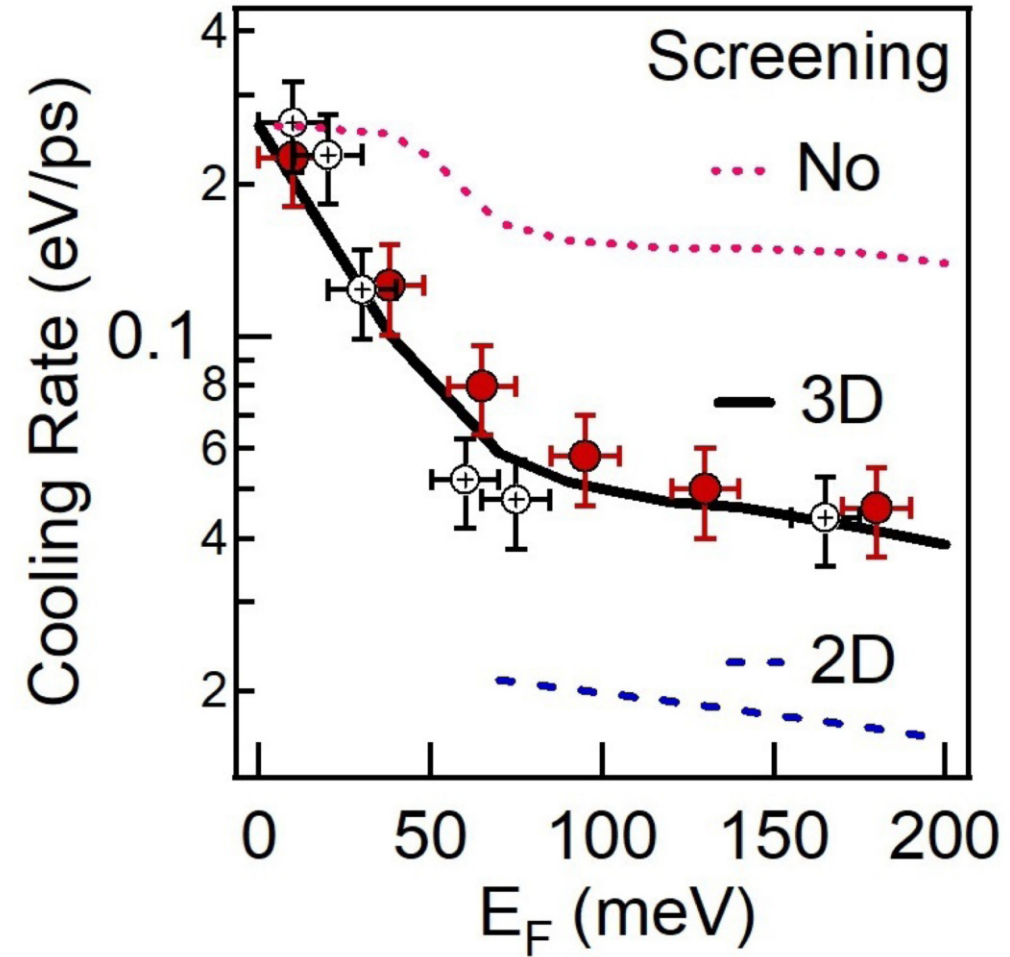
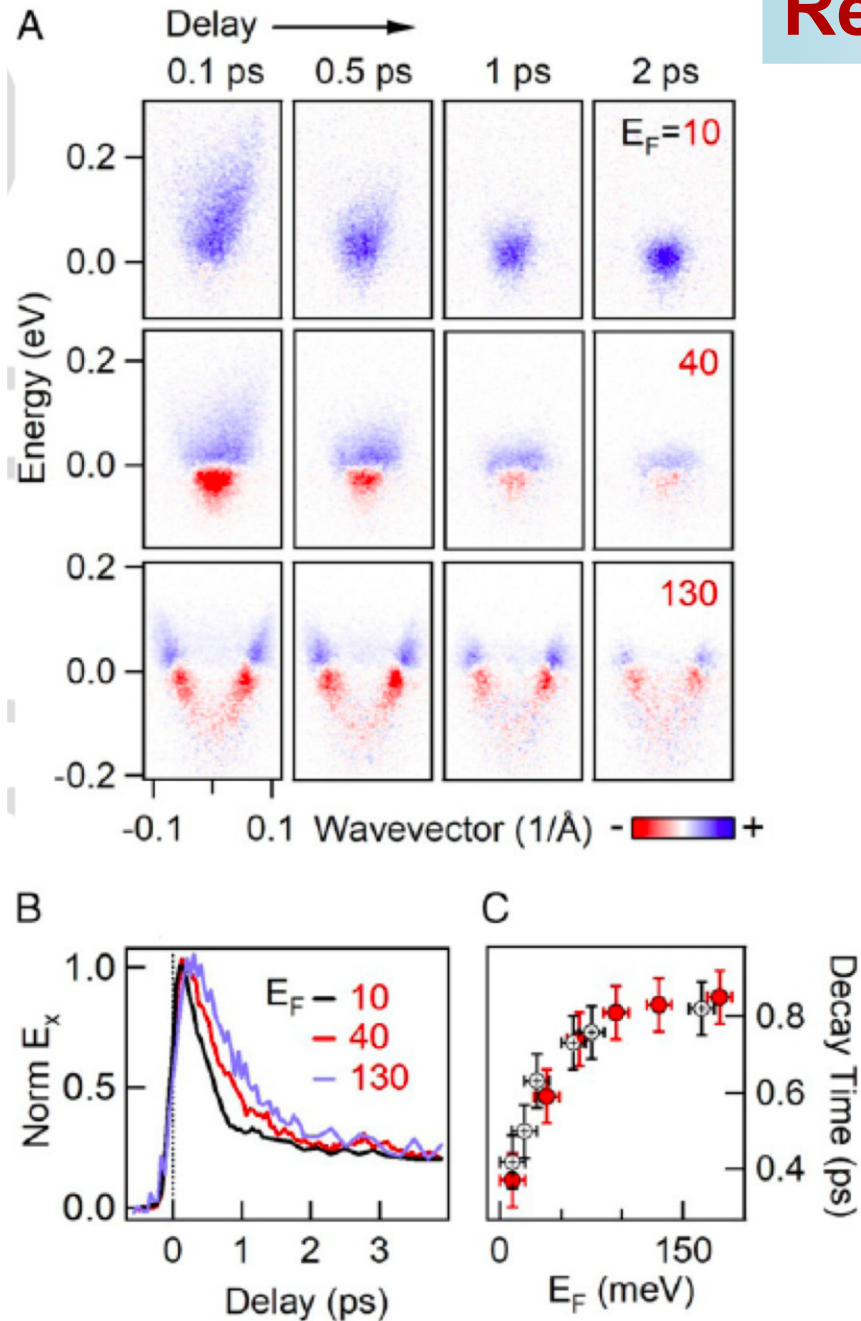


Low deposition:
photoexcited electrons
are non-thermal

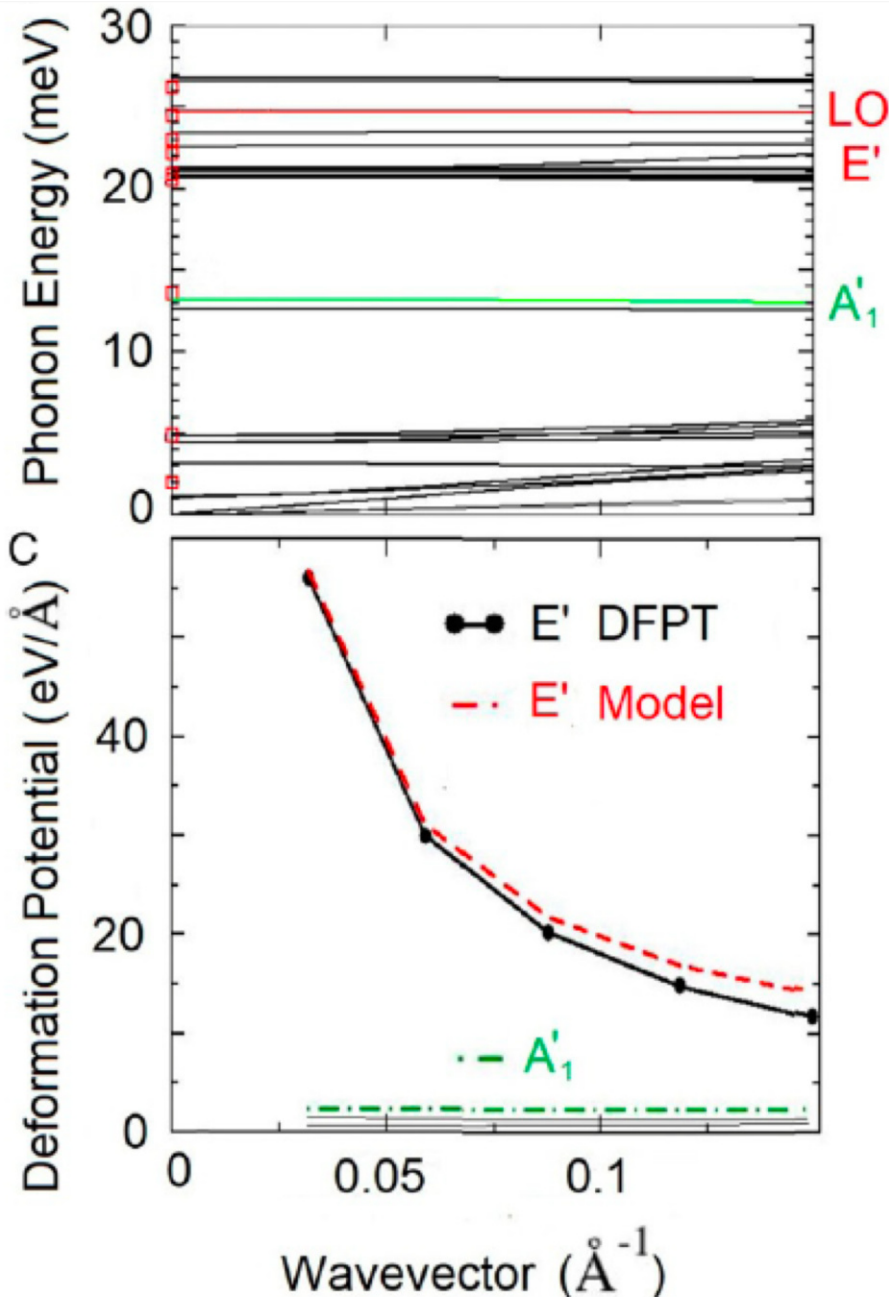
High deposition:
photoexcited electrons
are thermalized

3D Increasing Cs deposition → 2D

Relaxation dynamics of photoexcited electrons



Calculation: screened Fröhlich interaction



3D model:

$$|g_{fr}^{3D}(\mathbf{q})| = \frac{4\pi e^2}{V \epsilon_{bulk} |\mathbf{q}|} \sum_s \sum_{\lambda'} \frac{q_{\lambda'}}{|\mathbf{q}|} Z_{\lambda' \lambda s} \mathbf{e}_{\lambda}^s(\mathbf{q}) / \sqrt{2M_s \omega_{\mathbf{q}}}$$

Vogl, PRB 13 (1976).

3D screening:

$$\epsilon_{bulk}^{scr} = \epsilon_{bulk} \left(1 + \frac{(q_0^{3D})^2}{q^2} \right)$$

Thomas-Fermi

2D model:

$$|g_{fr}^{2D}(\mathbf{q})| = \frac{C_Z}{e_{eff}^0 + r_{eff} |\mathbf{q}_p|}$$

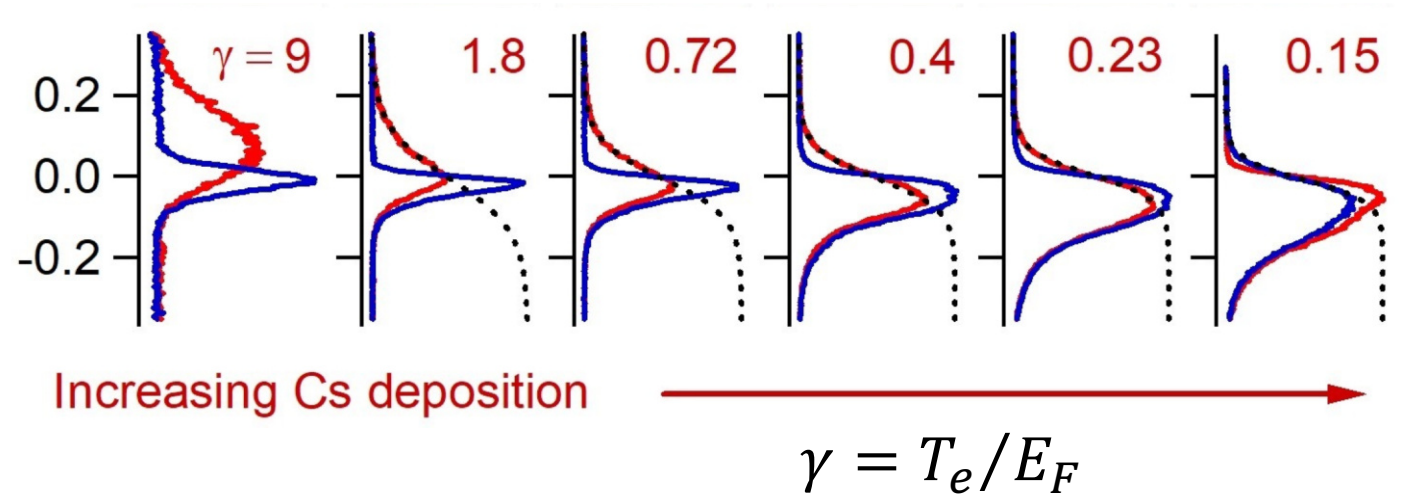
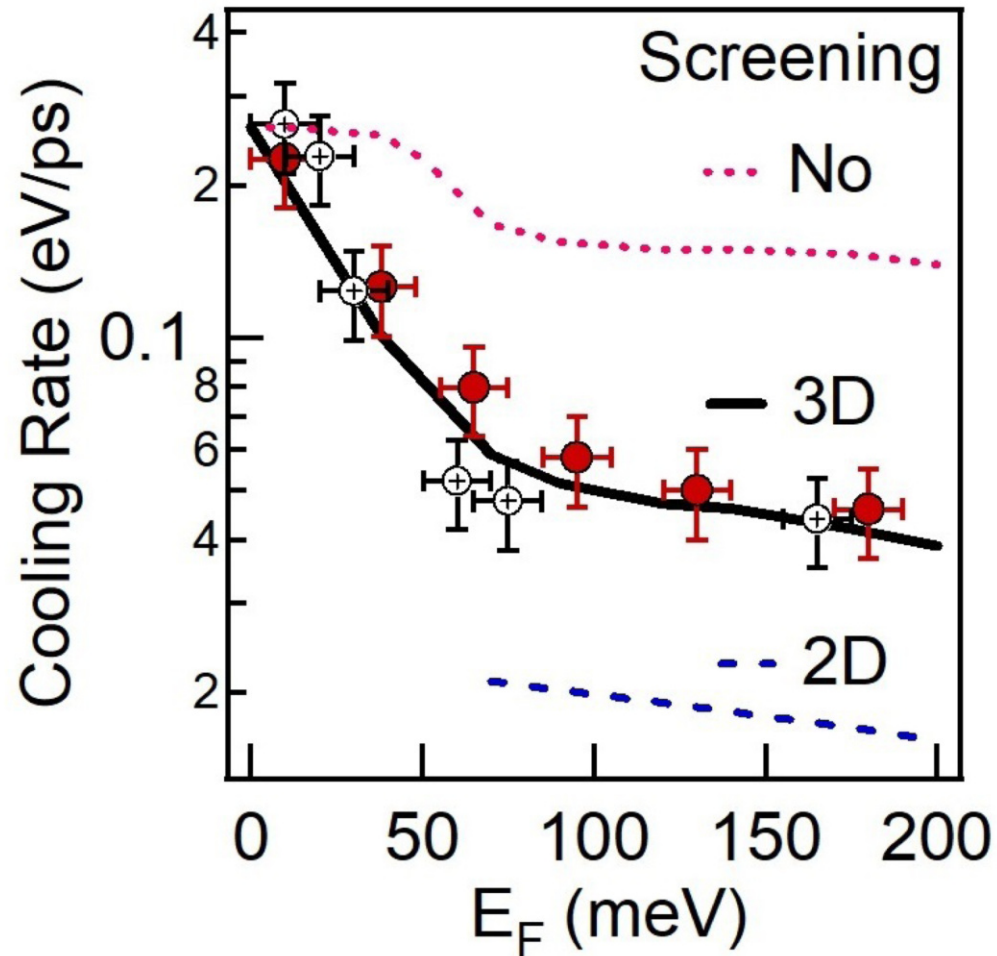
$$C_Z = \frac{2\pi e^2}{A} \times \sum_s \sum_{\lambda'} \frac{q_{\lambda'}}{|\mathbf{q}_p|} Z_{\lambda' \lambda s} \mathbf{e}_{\lambda}^s(\mathbf{q}) / \sqrt{2M_s \omega_{\mathbf{q}}}$$

Sohier, Calandra, Mauri, PRB 94 (2016)

2D screening:

Stern, PRL 18, 546 (1967)

Energy transfer in doped InSe



➡ Remote coupling of electrons to 3D phonons

Conclusion

Dynamics of relaxation of highly excited (or « hot » ?) electrons in Si and in InSe

- ➔ *The concept of hot electron ensemble allowed us to interpret the relaxation times of highly excited electrons in silicon.*
- ➔ *In Si, energy loss rate is determined by the DOS of the final electronic states. Negligible temperature dependence.*
- ➔ *In InSe, at excess energies below 0.7 eV, energy loss rate is determined by Fröhlich coupling.*
- ➔ *Doped InSe:*
 - ➔ *screening of polar coupling*
 - ➔ *remote coupling to 3D phonons*

Thank you for your attention!